



11) Publication number:

0 413 550 A3

## (12)

## **EUROPEAN PATENT APPLICATION**

21) Application number: 90308912.6

22 Date of filing: 14.08.90

(51) Int. Cl.<sup>5</sup>: **C08F 293/00**, C08G 77/22, C08G 77/382, C08G 77/442

Priority: 14.08.89 US 393550

Date of publication of application: 20.02.91 Bulletin 91/08

Ø Designated Contracting States:
DE FR GB

Date of deferred publication of the search report: 26.02.92 Bulletin 92/09

Applicant: MINNESOTA MINING AND MANUFACTURING COMPANY 3M Center, P.O. Box 33427 St. Paul, Minnesota 55133-3427(US)

② Inventor: Kumar, Ramesh C., c/o Minnesota Mining and Manufacturing Co. 2501 Hudson Road, P.O. Box 33427

St. Paul, Minnesota 55133-3427(US)

Inventor: Andrus, Milton H., Jr., c/o Minnesota

Mining and

Manufacturing Co. 2501 Hudson Road, P.O.

Box 33427

St. Paul, Minnesota 55133-3427(US)

Inventor: Mazurek, Mieczyslaw H., c/o

Minnesota Mining and

Manufacturing Co. 2501 Hudson Road, P.O.

Box 33427

St. Paul, Minnesota 55133-3427(US)

Representative: Baillie, Iain Cameron et al c/o Ladas & Parry, Altheimer Eck 2 W-8000 München 2(DE)

Siloxane iniferter compounds, block copolymers made therewith and a method of making the block copolymers.

The present invention provides novel siloxane iniferter compounds, block copolymers made therewith, and a method of making the block copolymers. The siloxane iniferter compounds can be represented by the formula

wherein

T and X are organic groups selected so that the T-X bond is capable of dissociating upon being subjected to an appropriate energy source to form a terminator free radical of the formula  $T^{\bullet}$  and an initiator free radical.

 $R_1$ ,  $R_2$ ,  $R_5$  and  $R_6$  are monovalent moieties selected from the group consisting of hydrogen,  $C_{1-4}$  alkyl,

 $C_{1-4}$  alkoxy and aryl which can be the same or are different:

 $R_3$  and  $R_4$  are monovalent moieties which can be the same or different selected from the group consisting of hydrogen,  $C_{1-4}$  alkyl,  $C_{1-4}$  fluoroalkyl including at least one fluorine atom and aryl;

Y is selected from the group consisting of -X-T and -Z wherein X and T are defined above and Z is an organic moiety that will not dissociate to form free radicals when subjected to said energy source; and m is an integer of at least 10.

The initiator free radical is capable of initiating free radical polymerization of free radically polymerizable monomer. The terminator free radical is insufficiently capable of initiating free radical polymerization of free radically polymerizable monomer but is capable of rejoining with the initiator free radical or a free radical polymer segment free radically polymerized with the initiator free radical.



## **EUROPEAN SEARCH REPORT**

EP 90 30 8912

tegory		rith indication, where appropriate, levant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. CI.5)
E		,		C 08 F 293/00 C 08 G 77/22 C 08 G 77/382
X	WORLD PATENTS INDEX LATEST Week 8550, Derwent Publications Ltd., London, GB; AN 85-314533 & JP-A-60 220 341 (NIPPON TELEG & TELEPH) 5 November 1985 * abstract * *		1-4	C 08 G 77/442
Α	March 1984, NEW YORK, ET AL.: 'Surface Photogra'	OLYMER SCIENCE vol. 29, no. 3, USA pages 877 - 889; H.INOUE fting of Hydrophilic Vinyl Monarbamated Polydimethylsiloxane' paragraph 2 * * * page 879,	1-4,7,8, 10	
X	US-A-3 445 496 (J. W. RYAN)  * column 2, line 25 - line 36; claim 4; examples 7,10 * *		1,4-6	
×	CHEMICAL ABSTRACTS, vol. 105, no. 20, 17 November 1986, Columbus, Ohio, US; abstract no. 173534S, H.INOUE ET AL.: 'Photografting of vinyl monomers into diethyl-dithiocarbamated polydimethylsiloxane' page 34; * abstract * & Kagaku to Kogyo (Osaka) 1986, 60(3), 81-90 *		1-4,7,8, 10	TECHNICAL FIELDS SEARCHED (Int. CI.5)  C 08 F C 08 G
D,A	GB-A-2 188 056 (GENERAL ELECTRIC COMPANY)  * claims 1-19 * *		1,7,8,10	
	The present search report has	been drawn up for all claims		
	Place of search	Date of completion of search	<u> </u>	Examiner
The Hague 10 [		10 December 91		KANETAKIS I.

- Y: particularly relevant if taken alone
   Y: particularly relevant if combined with another document of the same catagory
   A: technological background
   O: non-written disclosure
   P: intermediate document
   T: theory or principle underlying the invention

- D: document cited in the application
- L: document cited for other reasons
- &: member of the same patent family, corresponding document